

Message Text

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PAGE 01 TOKYO 07956 310932Z
ACTION OES-07

INFO OCT-01 EA-09 ISO-00 COME-00 EB-07 PA-02 USIA-15
CIAE-00 INR-07 NSAE-00 /048 W
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FM AMEMBASSY TOKYO
TO SECSTATE WASHDC 8197

UNCLAS TOKYO 7956

FOR OES/APT/SA; INR/DDC

DEPT. PASS USDOC/NBS FOR LINDAMOOD

E.O. 11652: N/A
TAGS: TECH, EQUIP, JA
SUBJECT: JAPANESE DEVELOPMENT OF NEW VLSI PRODUCTION TECHNOLOGY

REF: TOKYO 5209

1. THE VLSI TECHNOLOGY RESEARCH ASSOCIATION HAS ANNOUNCED SUCCESS IN DEVELOPING TECHNOLOGY WHICH INCREASES SPEED AND ACCURACY OF ELECTRON BEAM METHOD FOR MANUFACTURE OF INTEGRATED CIRCUITS. THE ANNOUNCEMENT INDICATES THAT THE NEW TECHNOLOGY ALLOWS PRINTING A CIRCUIT IN ONE TENTH THE TIME REQUIRED BY MACHINES USING STANDARD ELECTRON BEAM TECHNOLOGY. USING A SYSTEM OF PHYSICAL APERTURES AND AN ELECTROMAGNETIC LENS, THE NEW DEVICE PRODUCES AN ELECTRON BEAM WHICH PRINTS CIRCUITS AS A SERIES OF RECTANGLES. THE RECTANGLES ARE VARIABLE IN SIZE AND COVER MORE AREA THAN THE SERIES OF POINTS PRINTED BY OLDER TYPES OF MACHINES. SINCE MORE SURFACE AREA CAN BE EXPOSED IN THE SAME AMOUNT OF TIME, THE PRINTING IS DONE AT A MUCH HIGHER SPEED.

2. THE EQUIPMENT DEVELOPED BY THE ASSOCIATION CAN PRINT RECTANGLES OF ONE TO TWENTY-FIVE MICRONS IN WIDTH. THE
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PAGE 02 TOKYO 07956 310932Z

HOPE IS TO PRODUCE A MACHINE WHICH CAN PRINT LINES LESS THAN ONE MICRON IN WIDTH BY 1979. IT IS HOPED THAT IMPROVEMENTS IN THE ELECTROMAGNETIC LENS WILL ACCOMPLISH THIS REFINEMENT.

3. REPORTEDLY, RESEARCHERS AT THE PHYSICAL AND CHEMICAL RESEARCH INSTITUTE, TOGETHER WITH RESEARCHERS

FROM FUJITSU WERE THE MAJOR PARTICIPANTS IN THE DEVELOPMENT PROJECT, EMPLOYING COMPONENTS MADE BY JAPAN ELECTRON OPTICS LABORATORY AND FUJITSU. THE MINISTRY OF INTERNATIONAL TRADE AND INDUSTRY, WHICH IS SPONSORING THIS RESEARCH EFFORT, WILL CONTINUE TO SUPPORT THIS ACTIVITY FOR THREE MORE YEARS, WITH SUBSIDIES AND ADMINISTRATIVE GUIDANCE.

4. IBM IS SAID TO HAVE DEVELOPED SIMILAR PROCESS ABOUT ONE YEAR AGO. FYI: TERM "PRINTING" USED IN ABOVE MEANS EXPOSURE OF PHOTSENSITIVE LAYER TO ELECTRON BEAM RADIATION. END FYI.

5. EMBASSY WILL ATTEMPT TO OBTAIN MORE DETAILED TECHNICAL INFORMATION ON THE NEW PROCESS FOR TRANSMITTAL TO DEPT. SHOESMITH

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Message Attributes

Automatic Decaptioning: X
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Concepts: COMPUTERS
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Disposition Approved on Date:
Disposition Case Number: n/a
Disposition Comment:
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